

## USPAS course on Recirculated and Energy Recovered Linacs

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Electron Sources: Introduction, Parameters, Physics of Electron Emission







- Parameter space
  - FELs
  - light source
  - nuclear physics
  - ion cooling
  - electron-ion collider
- Emission
  - thermal
  - field
  - photoemission



Contents



# • Photoemission from semiconductors

- Introduction
- Inelastic scattering: electron-electron and electron-phonon
- Negative electron affinity
- Thermal emittance
- Diffusion model and temporal response
- Lifetime of the photocathode



Contents



## Introduction

With a short-lived ( $\leq \mu s$ ) electron life-cycle in R&ERLs, the emphasis for delivering the beam of appropriate quality for a given application shifts almost entirely on the injector.

- One way to define an injector: a part of the R&ERL up to (and including) the merge with the returning high-energy beam.
- The injector determines many of the key properties of the beam (can be degraded downstream, but never improved!)
  - beam current & timing structure
  - horizontal & longitudinal emittances
  - polarized & magnetized beam

Since R&ERLs can be applied to a host of different applications, each with its own parameter set from the injector, no single injector design or approach can be adequate.

Thermal Emission Photoemission Field Emission Injectors are found at the interface of various disciplines & techniques:

- solid state & material science (cathode physics)
- lasers (photoemission)
- complex beam dynamics: space charge, single species plasma, governed by its Debye length and plasma frequency
- high field guns (part of the injector where beam is born), surfaces at ultrahigh gradients
- efferson Pal 'usual' accelerator physics



## Applications

## R&ERL applications

- Light sources
  - Spontaneous
  - Free electron lasers
- Nuclear physics (CEBAF)
- Electron cooling of ions
- Electron-ion collider

Beam parameters vary from sub-pC to several nC charge / bunch, less than mA to Ampere average current, may have 'special' requirements: polarization and magnetized beam





$$\lambda = \lambda_{p} (1+K^{2}/2) / 2\gamma^{2} \quad \text{typical } \lambda_{p} \ge 2 \text{ cm}$$

$$\downarrow$$
Pierce  $\rho = \left[\frac{K^{2}[JJ]r_{e}n_{e}\lambda_{p}^{2}}{32\pi\gamma^{3}}\right]^{1/3} \quad \longleftrightarrow \quad N_{p}, \text{ Gain}$ 

$$\epsilon_{x,y} = \lambda/4\pi \quad \Delta E/E = 1/4N_{p} \quad I_{peak}$$

$$\downarrow \qquad \downarrow \qquad \downarrow \qquad \downarrow$$

$$\epsilon_{x,y} = \epsilon_{n} / \gamma, \quad q, \quad \sigma_{z}$$
Oscillator HGHG SASE

FELS

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$$\varepsilon_{x,y} = \lambda/4\pi \quad \Delta E/E = 1/4N_p \quad I_{peak}$$

FELs (contd.)



Longer wavelength  $\rightarrow$  high reflectivity mirrors  $\rightarrow$  oscillator configuration  $\rightarrow$  short undulator

 $\varepsilon_n \sim 10 \ \mu m, E \le 100 \ MeV$ q ~ 0.1 nC for  $\lambda \sim 1 \mu m$ 

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Shorter wavelength (XUV and down)  $\rightarrow$  high gain  $\rightarrow$  long

High Gain

undulator  $\rightarrow$  more stringent specs

 $\varepsilon_n \sim 1 \ \mu m, E > GeV$ q ~ 1 nC for  $\lambda \sim 10 \ nm$ 

For high power FELs I ~ 0.1-1 A

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 $3^{rd}$  GLS storage rings, workhorse of X-ray science, are spontaneous emission sources (photons produced =  $N_e \times$ single electron radiation). Various figures of merit can be used to characterize the source, e.g.

Flux [ph/s/0.1%bw]Brightness [ph/s/0.1%/mm²/mr²]
$$\propto I$$
 $\propto I/(\epsilon_x \oplus \lambda/4\pi)(\epsilon_y \oplus \lambda/4\pi)$ 

Improving flux beyond what is possible with a storage ring is unlikely, but brilliance can be improved (presently best values  $10^{20}$ – $10^{21}$  ph/s/0.1%/mm<sup>2</sup>/mr<sup>2</sup>).

 $\varepsilon_n \sim 0.6 \ \mu m, q \sim 0.08 \ nC, I \sim 100 \ mA, E \sim 5 \ GeV$ for brilliance of ~ 10<sup>22</sup> ph/s/0.1%/mm<sup>2</sup>/mr<sup>2</sup>



## Nuclear physics

## Electrons are a probe.

E = 6 GeV  $I = 200 \ \mu\text{A}$   $q < 0.3 \ \text{pC}$   $\Delta E/E = 2.5 \times 10^{-5}$ Polarization > 75 %

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Polarization is given by  $\frac{I(\uparrow) - I(\downarrow)}{I(\uparrow) + I(\downarrow)}$ 

where  $I(\uparrow)$  is the number of electrons with spin 'up' and  $I(\downarrow)$  is the number of electrons with spin 'down' along a given axis.



## Electron cooling of ions

- There is no radiative cooling in ion storage rings due to their large mass. One way to reduce ions phase space volume is to co-propagate ions with a bunch of cold electrons (same  $\beta = v/c$ ). In the rest frame, the picture resembles two-species plasma with different temperatures  $T_{ion} > T_{electron}$  (interaction will heat up electrons and cool down ions).
- High density of electrons is required for tolerable cooling rates.
- Interaction takes place in a long focusing solenoid. To avoid enlarged 2D emittance a so-called 'magnetized' beam is needed from the source. We will discuss magnetized beam and Busch's theorem later in this lecture.





## Electron cooling of ions (BNL)







## Electron-Ion collider



E = 2-10 GeV I ~ 100s mA  $\varepsilon_n$  ~ 10s mm-mrad polarized electrons from the gun





• The underlying feature of present and future R&ERLs is CW operation  $\rightarrow$  high rep. rate, high current

• FELs: need a beam close to the diffraction limit  $\rightarrow$  emittance; need high peak current to lase (kA)  $\rightarrow$  charge per bunch, longitudinal emittance for low final/injection energy ratio

• ERL spontaneous LS: beam brightness is paramount  $\rightarrow I/\epsilon_x \epsilon_y$ ; medium to low charge per bunch preferred

- Electron cooling: high bunch charge (many nC) and current (0.1-1 Ampere); magnetized beam
- Electron-ion collider: polarized source with high average current





- It is literally impossible to cover all the areas circumscribed by injectors needed by various R&ERL in the framework of this course
- We'll concentrate on unique challenges of ERL sources, which mainly demand
  - High average current
  - Simultaneously with ultra-low emittance
- The choice of electron emission process is a key to subsequent electron source design
- But first let's discuss very briefly the state-of-the-art





## State-of-the-art: BOEING gun

#### Photocathode Performance:

Photosensitive Material: 5% to 12% Ouantum Efficiency: Peak Current: Cathode Lifetime: Angle of Incidence: Gun Parameters: 26 MV/meter Cathode Gradient: Cavity Type: Number of cells: 4 RF Frequency: Final Energy: RF Power: Duty Factor: Laser Parameters: Micropulse Length: 53 ps, FWHM  $27 \times 10^6$  Hertz Micropulse Frequency: Macropulse Length: 10 ms Macropulse frequency: 30 Hertz Wavelength: 527 nm Cathode Spot Size: 3-5 mm FWHM Temporal and Transverse Distribution: Micropulse Energy: 1% to 5% Energy Stability: Pulse-to-pulse separation: 37 ns  $27 \times 10^6$  Hertz Micropulse Frequency: Gun Performance:

> Emittance (microns, RMS): Charge:

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#### K<sub>2</sub>CsSb Multialkali

45 to 132 amperes 1 to 10 hours near normal incidence

Water-cooled copper  $433 \times 10^6$  Hertz 5 MeV(4-cells)  $600 \times 10^3$  Watts 25%, 30 Hertz and 8.3

gaussian, gaussian 0.47 microjoule

> 5 to 10 for 1 to 7 nCoulomb 1 to 7 nCoulomb 5 MeV 100 to 150 keV

## 433 MHz RF Gun



#### 32 mA avg. current



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# State-of-the-art: JLAB FEL inj.

# 500 kV (350) DC gun

- Cs:GaAs photocatode
- max current 9.1 mA, routine 5 mA
- best simulated emittance 5 μm, measured ×2 larger at 60 pC
- work on 100 mA gun underway to drive high power IR FEL



9.1 mA avg. current





# Cathode figures of merit

- available current density
- energy and momentum distribution of emitted electrons
  - transverse temperature

$$\varepsilon_{n,th} = \sigma_{\perp} \sqrt{\frac{E_{th}}{mc^2}}$$

• lifetime (resistance to contamination)





## Emission: thermal in metals



Richardson-Dushman equation (1923)

$$A = 120 \text{ A/(cm^2 K^2)}$$

$$Current \text{ density} \quad J = AT^2 \exp\left[-\frac{e\varphi_W}{kT}\right] \quad \varphi_W = 4.5 \text{ V (tungsten)}$$

$$\varphi_W = 2.0 \text{ V (dispenser)}$$



External field lowers work function  $\varphi_W^* \to \varphi_W - \Delta \varphi$ 

Schottky correction

$$\Delta \varphi = \sqrt{\frac{eE}{4\pi\varepsilon_0}} \quad \Delta \varphi[V] = 0.038\sqrt{E[MV/m]}$$



Schottky correction does not include probability of escaping from a finite width potential barrier that follows from quantum mechanics. In 1928 Fowler and Nordheim have published a paper where they derived current density from this effect.





Interestingly, F-N dependence of field emission with E is the same as the functional R-D dependence of thermal emission with T.

In reality, field emission fits F-N dependence if  $E \rightarrow E\beta$ .  $\beta$  is known as an enhancement factor that translates macroscopic field E to a local value (local geometry dependant).

In summary,

$$J_{thermal} = AT^{2} \exp\left[-\frac{e\varphi_{W}}{kT}\right]$$
$$J_{Schottky} = AT^{2} \exp\left[-\frac{e(\varphi_{W} - B\sqrt{\beta E})}{kT}\right]$$
$$J_{field} = C\beta^{2}E^{2} \exp\left[-\frac{D}{\beta E}\right]$$





Photoemission offers several advantages over thermal/field emission:

- Higher current density
- Bunched beam is generated through a laser with appropriate time structure. No need for chopping / extensive bunching as in the case of thermal emission (shortest pulse available through a grid pulser is ~ ns, while L-band RF needs bunches ~10 ps long – readily available from photocathodes).
- Colder beam (lower thermal emittance) is possible
- Polarized electrons from special photocathodes

Interesting historical overview of photocathode development Alfred H. Sommer, Brief history of photoemissive materials, SPIE Proc 2022 (1993) pp. 2-17 USPAS'08 R & ER Linacs



 $I[\text{mA}] = \frac{\lambda[\text{nm}]}{124} \times P_{laser}[\text{W}] \times \eta[\%] \qquad \qquad \frac{N_e}{N_{ph}}$ 

Photocurrent

- For *metals* such as copper work function is  $4.5 \text{ eV} \rightarrow \text{UV}$  light is required (frequency multiplication in nonlinear medium crystals)
- Furthermore,  $\eta$  is low (< 10<sup>-3</sup>) due to electron-electron scattering in conduction band (1/2 energy lost per collision on average)
- Metals have very fast response time (fs)
- Thermal emittance numbers vary, values quoted for thermal energy  $E_{th} = 0.2-0.7 \text{ eV}$
- In short, metals (Cu, Mg, etc.) are suitable for pulsed applications, but is a poor choice for a high average current gun



## Photoemission: semiconductors



Energy banding of allowed levels in diamond as a function of spacing between atoms

Gap and availability of electrons in conduction band determines whether material is Metal: ne ~  $10^{23}$  cm<sup>-3</sup> Semiconductor: gap < 3 eV; n<sub>e</sub> (n<sub>h</sub>) <  $10^{20}$  cm–3 Insulator: gap > 3 eV; negligible n<sub>e</sub> and n<sub>h</sub>

Good quantum efficiency (10s %) available from semiconductor photocathodes ( $K_2CsSb$ ,  $Cs_2Te$ , GaAs) & lower photon energy due to a smaller gap



## Spicer's three step model





Absorption edge of GaAs at room temperature.



(1) photon excites electron to a higher-energy state;
(2) electron-phonon scattering (~0.01–0.05 eV lost per collision);
(3) escape with kinetic energy in excess to E<sub>vac</sub>

In GaAs the escape depth is sufficiently long so that photo-excited electrons are *thermalized* to the bottom of the conduction band before they escape.

Response time ~  $(10^{-4} \text{ cm})/(10^7 \text{ cm/s}) =$ 10 ps (wavelength dependant)



- electron-electron scattering, lead to large energy loss per single collision (occurs in metals);
- (2) electron-phonon scattering, takes multiple scattering events to deplete electron excessive energy;
- (3) "magic window" in semiconductors, if takes an excess kinetic energy >  $E_{gap}$  for e<sup>-</sup>/e<sup>-</sup> scattering to occur, so electrons excited with  $E_{vac} < KE < E_{VBM} + 2E_{gap}$  have good chances of escape

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## Negative electron affinity

Surface condition induces a space charge, which may bend the bands either up or down (bottom of conduction band in the bulk relative to  $E_{vac}$  is called electron affinity).

If thickness of a low  $\phi_W$  material << mean free path  $\rightarrow e^-$  can traverse the surface material without much loss  $\rightarrow$  better quantum efficiency / reduced threshold







## Bend-banding





GaAs photocathode





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## Thermal emittance



relates laser spot size to emittance



### Temporal response

- Because the escape length from high QE cathodes is long, one may expect a long temporal tail
- Indeed, long emission tails have been measured for GaAs excited with near band gap energy photons P. Hartmann et al., J. Appl. Phys. 86 (1999) 2245





## Diffusion model

$$\frac{\partial c(h,t)}{\partial t} = D \frac{\partial^2 c(h,t)}{\partial h^2}$$
subject to:  

$$c(h,t=0) = c_0 e^{-\alpha h}$$

$$c(h=0,t) = 0$$

$$I(t) \propto \frac{\partial}{\partial t} \int_{0}^{\infty} c(h,t) dh.$$

$$I(\kappa) \propto \frac{1}{\sqrt{\pi\kappa}} - \exp(\kappa) \operatorname{erfc}(\sqrt{\kappa})$$

$$\kappa \equiv t/\tau, \text{ where } \tau \equiv \alpha^{-2}D^{-1}$$

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Wavelength (nm)	$\tau \ (\mathrm{ps})$	Comment
860	$76{\pm}26$	$V_{gun} = 200 \text{ kV}$
860	$69 \pm 22$	$V_{gun} = 250 \text{ kV}$
785	$11.5 \pm 1.2$	$V_{gun} = 200 \text{ kV}$
785	$9.3 \pm 1.1$	$V_{gun} = 250 \text{ kV}$
710	$5.8 \pm 0.5$	$V_{gun} = 200 \text{ kV}$
710	$5.2 \pm 0.5$	$V_{gun} = 250 \text{ kV}$
520	$\leq 1$	upper estimate placed
460	$\leq 0.14$	upper estimate placed

#### TABLE I: Results of data fitting for GaAs response time.



### GaAsP at 520 nm



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## Polarized photoelectrons

In strained GaAs, spin degeneracy of two states ( $\Gamma_{6.7}$ ) is removed.

Circularly polarized light of the right wavelength produces polarized electrons (> 80% polarization measured). Low QE.

Doping is important to increase carrier density to avoid a so-called surface charge limit.





 $( \land )$ 

signal

FARC

1.0

Ο.



## Cathode lifetime

